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UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Cecile BERNE et al.

Confirmation No.: 2144

Application No.: 10/733,431

Group Art Unit: 2826

Filing Date: December 10, 2003

Examiner: Evan T. Pert

For: TWO-STAGE ANNEALING METHOD  
FOR MANUFACTURING  
SEMICONDUCTOR SUBSTRATES

Attorney Docket No.: 4717-5499

**SUBMISSION OF FORMAL DRAWINGS**

**Mail Stop Issue Fee**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Notice of Allowability mailed April 29, 2005, submitted herewith is one (1) sheet of formal drawings including Figs. 6 and 7. The drawings have been corrected as required by the Examiner to add the legend "Prior Art" to each of Figs. 6 and 7. Applicants respectfully request that the attached sheet of drawings be substituted for the sheet of drawings originally filed in this application that includes Figs. 6 and 7.

No fee is believed to be due for this submission. Should any fees be required, however, please charge such fees to Winston & Strawn LLP Deposit Account No. 50-1814.

Respectfully submitted,

5/5/05  
Date

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